

Form PTO-1449

Docket Number (Optional)

Application Number

TSMC-02-218

10/689,431

Applicant

Hung-Dar Su et al.

Filing Date

10/20/03

Group Art Unit

2829

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

(Use several sheets if necessary)

U. S. PATENT DOCUMENTS

| | DOCUMENT NUMBER | DATE | NAME | CLASS | SUBCLASS | ALING DATE IF APPROPRIATE |
|----|-----------------|----------|--------------------|-------|----------|------------------------------|
| MT | 5485097 | 1/16/96 | Wang | 324 | 765 | 8/8/94 |
| | 6456105 | 9/24/02 | Tao | 324 | 769 | 8/8/00 |
| | 6472236 | 10/29/02 | Wang et al. | 438 | 14 | 7/13/01 |
| | 6066952 | 5/23/00 | Nowak et al. | 324 | 458 | 9/25/97 |
| | 5793675 | 8/11/98 | Cappellotti et al. | 365 | 185.09 | 4/1/97 |
| | 6339339 | 1/15/02 | Maeda | 324 | 769 | 1/22/01 |
| | 6472233 | 10/29/02 | Ahmed et al. | 438 | 14 | 6/5/00 |
| MT | 6011404 | 1/4/00 | Ma et al. | 324 | 765 | 7/3/97 |
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FOREIGN PATENT DOCUMENTS

| | DOCUMENT NUMBER | DATE | COUNTRY | CLASS | SUBCLASS | Translation | |
|--|-----------------|------|---------|-------|----------|-------------|----|
| | | | | | | YES | NO |
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OTHER DOCUMENTS (Including Author, Title, Date, Portion of Pages, Etc.)

| | | |
|----|---|---|
| MT | - | "Gate Dielectric Capacitance-Voltage Characterization Using the Model 4200 Semiconductor Characterization System", Keithley, Application Notes Series, No. 2239. (no month/year) |
| | - | Agilent Technologies Impedance Measurement Handbook, 2nd Edition, Application Note 5950, staff, Agilent Technologies Co., Ltd., Palo Alto, CA, Copyright 2000, 5-12 to 5-14. (no month) |
| MT | | |

EXAMINER

Muh Tang

DATE CONSIDERED

01/05/05

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

